



PMMA Polymers: 50K, 200K, 600K, 950K corresponding
E-Beam Resist Series: AR-P 631, 641, 661, 671 (chlorobenzene)
 AR-P 632, 642, 662, 672 (anisole) and AR-P 639, 649, 669, 679 (ethyl lactate)

1. General Description

The E-beam Resists Series AR-P 631-671, AR-P 639-679 and AR-P 632-672 are positive working resists suitable for all kinds of e-beam applications. These resists are filtered to a particle size of 0.2 µm.

The resists are designed to meet critical geometry requirements of mask production in the advanced integrated circuit fabrication. The PMMA-polymer layers are distinguished by an excellent adhesion on glass, silicon and metal.

The polymer 50K has an about 20 % higher sensitivity as the polymer 950K. The developed patterns are thermal stable up to 120 °C.

The resists AR-P 631-671, AR-P 639-679 and AR-P 632-672 can be used for multilayer processes and planarisation. Resists with low solids content for resist thickness down to 30 nm are suitable especially for the nanometer lithography.

2. Chemical Composition

Polymers based on methyl methacrylate with different molecular weights, dissolved in chlorobenzene (AR-P 631-671, Flash point (Fp): 28°C, anisole (AR-P 632-672, Fp: 43°C), ethyl lactate (AR-P 639-679, Fp: 36°C).

3. Process Description and Storage

• Coating	6000-2000 rpm in air conditioned working areas at 20-25 °C and a humidity of 30-50 % (☞ Tab. 2).
• Baking	150-190 ± 2 °C, 60 min convection oven or 150-180 ± 2 °C, 2-5 min hot plate.
• Exposure	With usual devices for e-beam lithography. ☞ A typical dose to clear is about 80-100 µC/cm ² (20 kV, resist thickness 1.0 µm).
• Development	1-3 minutes with the developers AR 600-55 (faster) or AR 600-56 (slower)
• Stopping	30 seconds with the stopper AR 600-60
• Post bake	For special processes 30 minutes in a convection oven at 110 °C. ☞ For high etching resistance in wet chemical and plasma chemical etch processes.
• Cleaning	Substrates and equipment baked < 150 °C can be cleaned with Thinner AR 600-01 (AR-P 631-671), AR 600-02 (AR-P 632-672), AR 600-09 (AR-P 639-679) or Remover AR 600-70.
• Removing	Baked PMMA films: Remover AR 600-70 or AR 300-70 (a stronger remover which can be heated to up to 60 °C in order to enhance effectivity). ☞ Hard-baked films (> 200 °C) require the use of oxidising acids (aqua regia, piranha, warm chromium sulphuric acid solutions), or a treatment with oxygen plasma.
• Storage	Functionality guaranteed for 6 months from date of sale if stored dry at a constant temperature between 10 - 22°C.

4. Disposal and Safety References

Liquid or solid wastes have to be disposed at proper deposit places or by controlled combustion in officially authorized plants. Resists and thinner contain organic solvents. Adequate ventilation in the working area is demanded. Avoid direct contact with products and their vapours.

Wear chemical goggles and protective gloves! Please ask for safety data sheets!

Tab. 2 Spezifikations of 50K, 200K, 600K and 950K in chlorobenzene, anisole und ethyl lactate

as of 02.07.12

PMMA	E-Beam Resist	Solids	Solvent	Viscosity	Film thickness [μm]				Density	
Molec.weight	AR-P	content [%]		25°C [mPas]	1000 rpm	2000 rpm	4000 rpm	6000 rpm	20°C [g/cm ³]	
50K	631.01	1,0	chlorobenzene	0,9		0,02	0,02	0,01	1,104	
	631.04	4,0		1,3		0,13	0,09	0,08	1,107	
	631.06	6,0		1,9		0,23	0,17	0,14	1,110	
	631.09	9,0		3,1	0,57	0,41	0,30	0,25	1,112	
	632.01 new	1,0	anisole	1,2	0,02	0,02	0,02	0,01	0,992	
	632.04 (new)	4,0		1,8	0,11	0,08	0,06	0,05	0,995	
	632.06 new	6,0		2,3	0,21	0,16	0,11	0,09	0,997	
	632.09 new	9,0		3,5	0,38	0,27	0,20	0,17	0,999	
		632.12 new	12,0		5,1	0,60	0,42	0,31	0,25	1,001
		639.01	1,0	ethyl lactate	1,4	0,02	0,02	0,02	0,01	0,964
	639.04	4,0	2,2		0,16	0,12	0,08	0,07	0,970	
200K	641.01	1,0	chlorobenzene	1,4		0,04	0,02	0,01	1,104	
	641.04	4,0		4,4		0,23	0,16	0,13	1,108	
	641.06	6,0		7,9		0,38	0,28	0,26	1,110	
	641.07	7,0		11,0		0,52	0,37	0,31	1,110	
		641.09	9,0		17,4	1,13	0,83	0,59	0,48	1,112
	642.01 new	1,0	anisole	1,9	0,03	0,02	0,02	0,01	0,992	
	642.03 new	3,0		4,8	0,13	0,09	0,07	0,05	0,994	
	642.04 (new)	4,0		6,8	0,21	0,15	0,11	0,08	0,996	
	642.06 new	6,0		12,8	0,41	0,29	0,21	0,17	0,997	
	642.07 new	7,0		16,5	0,53	0,37	0,27	0,22	0,998	
	642.09 new	9,0		30,3	0,85	0,59	0,41	0,35	0,999	
		642.12 new	11,0		62,3	1,51	1,08	0,78	0,63	1,002
	649.01	1,0	ethyl lactate	1,9		0,03	0,02	0,01	0,964	
	649.04	4,0		5,8	0,25	0,2	0,15	0,12	0,970	
600K	661.01	1,0	chlorobenzene	2,2		0,04	0,03	0,02	1,104	
	661.04 (new)	4,0		13,7		0,32	0,23	0,19	1,108	
	661.06	6,0		28,2		0,67	0,48	0,39	1,110	
	661.08	8,0		76,0		1,29	0,93	0,74	1,120	
		661.09	9,0		105	2,58	1,75	1,25	1,00	1,113
	662.01 new	1,0	anisole	2,6	0,03	0,02	0,02	0,01	0,991	
	662.04 new	4,0		12,2	0,28	0,22	0,14	0,09	0,995	
	662.06 new	6,0		31,2	0,59	0,41	0,29	0,25	0,998	
	662.09 new	9,0		82,5	1,27	0,91	0,62	0,54	1,003	
		662.11 new		11,0		158,8	2,14	1,47	1,04	0,88
	669.01	1,0		ethyl lactate	2,5		0,03	0,02	0,02	0,965
	669.04	4,0	15,6			0,31	0,22	0,18	0,970	
	669.06	6,0	68,0			0,74	0,52	0,42	0,975	
	669.07	7,0	128		1,66	1,07	0,74	0,60	0,978	
950K	671.01	1,0	chlorobenzene	3,2		0,04	0,03	0,02	1,105	
	671.02	2,0		7,3		0,13	0,09	0,07	1,106	
	671.04	4,0		23,2		0,43	0,31	0,26	1,108	
	671.05	5,0		57,0		0,69	0,49	0,39	1,109	
	671.06	6,0		86,0		0,97	0,68	0,54	1,110	
	671.07	7,0		135		1,37	0,97	0,78	1,111	
		671.09	9,0		285	3,70	2,40	1,70	1,34	1,113
	672.01	1,0	anisole	3,8	0,05	0,04	0,03	0,02	0,988	
	672.02	2,0		8,8	0,12	0,09	0,07	0,06	0,991	
	672.03	3,0		15,5	0,22	0,17	0,13	0,10	0,994	
	672.045	4,5		46,2	0,41	0,32	0,23	0,19	0,998	
	672.05	5,0		63,1	0,65	0,45	0,32	0,26	1,000	
	672.08	8,0		211	1,65	1,21	0,87	0,69	1,005	
		672.11 (new)	11,0		503	3,94	2,82	1,87	1,42	1,007
		679.01	1,0	ethyl lactate	3,4	0,05	0,04	0,03	0,02	0,965
	679.02	2,0	7,8		0,12	0,10	0,07	0,06	0,967	
	679.04	4,0	43,4		0,63	0,40	0,27	0,22	0,970	

The bold faced type resists of the series are standard products, their prices are included in the price list. All the other resists are delivered with a 25% added regular price in comparison with next higher solids content. With effect from 2013, Allresist will gradually replace resists in chlorobenzene by resists in anisole for health and environmental reasons. Due to our considerably extended range of anisole products with varying solid matter content, switching to anisole is already possible in 2012.

Spezifikation von 50K, 200K, 600k und 950K in chlorobenzene

Resist Thickness by 4000 rpm depending on solids content

